

	Type	L #	Hits	Search Text	DBs	Time Stamp
1	BRS	L1	154207	arc or antireflect	USPAT	2000/07/03 13:36
2	BRS	L2	67	polyimide same etch\$4 same (chlorine or Cl2 or CF4 or CHF3 or SF6 or CH2F2)	USPAT	2000/07/03 14:19
3	BRS	L3	1210	(barc or ARc) same organic	USPAT	2000/07/03 14:05
4	BRS	L4	0	3 and 2	USPAT	2000/07/03 14:05
5	BRS	L5	0	CHF3 with (CL2 OR CHLORINE) with (ar or argon)	USPAT	2000/07/03 14:08
6	BRS	L6	10	"CHF.sub.3" with (chlorine or"Cl.sub.2") with (Ar or Argon)	USPAT	2000/07/03 14:09
7	BRS	L7	48	(("CHF.SUB.3" WITH (ARGON OR AR)) WITH ("CL.SUB.2" OR CHLORINE))	USPAT	2000/07/03 14:10
8	BRS	L8	1	3 and 7	USPAT	2000/07/03 14:10
9	BRS	L9	2	BARC SAME (CH2F2 OR CHF3 OR CF4 OR SF6 OR CL2 OR CHLORINE) SAME ETCH\$4	USPAT	2000/07/03 14:23
10	BRS	L10	292	polyimide SAME (CH2F2 OR CHF3 OR CF4 OR SF6 OR CL2 OR CHLORINE or C2F6 SAME ETCH\$4)	USPAT	2000/07/03 14:24

	Type	L #	Hits	Search Text	DBs	Time Stamp
1	BRS	L1	12074	((aluminum or Al) or (Cu or copper) or (titanium or TI)) same (ARC or antireflect)	USPAT	2000/07/03 09:07
2	BRS	L2	295	1 same (photoresist or resist)	USPAT	2000/07/03 08:45
3	BRS	L3	56	"CHF.sub.3" same (chlorine or "cl.sub.2") same (Ar or argon) same (helium or He)	USPAT	2000/07/03 08:48
4	BRS	L4	0	2 and 3	USPAT	2000/07/03 08:48
5	BRS	L5	22	((("CHF.SUB.3" with (HELIUM OR HE)) with (ARGON OR AR)) with ("CL.SUB.2" OR CHLORINE))	USPAT	2000/07/03 08:49
6	BRS	L6	0	2 and 5	USPAT	2000/07/03 08:48
7	BRS	L7	48	"CHF.SUB.3" with (ARGON OR AR) with ("CL.SUB.2" OR CHLORINE)	USPAT; EPO; JPO	2000/07/03 08:50
8	BRS	L8	3	1 and 7	USPAT	2000/07/03 08:52
9	BRS	L9	0	7 same (ARC or antireflect)	USPAT	2000/07/03 08:53
10	BRS	L10	37	2 and "CHF.sub.3"	USPAT	2000/07/03 08:54
11	BRS	L11	24	10 and (chlorine or "Cl.sub.2")	USPAT	2000/07/03 08:55
12	BRS	L13	5	12 and "CHF.sub.3"	USPAT	2000/07/03 09:09
13	BRS	L12	156	(ANTIREFLECT OR ARC) SAME polyimide	USPAT	2000/07/03 09:13